Attorney Docket No. 008401 08

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In re Application of: Kenneth S. Collins, Hiroji Hanawa, Kartik Ramaswamy,
Andrew Nguyen, Amir Al-Bayati, Biagio Gallo, and Gonzalo
Antonio Monroy

Entitled: PLASMA IMMERSION ION IMPLANTATION SYSTEM INCLUDING A
CAPACITIVELY COUPLED PLASMA SOURCE HAVING LOW
DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE

Attorney Docket No.: 008401 08

Sir:

Enclosed herewith for filing is a patent application entitled PLASMA IMMERSION ION IMPLANTATION SYSTEM INCLUDING A CAPACITIVEY COUPLED PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE including 134 pages of specification, 26 claims and abstract, and 85 sheets of drawings (Figures 1-112).

This application is being filed missing parts and specifically without a declaration by the inventors and without a filing fee. The application is being filed in the names of the inventors, Kenneth S. Collins, Hiroji Hanawa, Kartik Ramaswamy, Andrew Nguyen, Amir Al-Bayati, Biagio Gallo, and Gonzalo Antonio Monroy.

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Dated: August 22, 2003

Respectfully submitted,

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